	Hits	Search Text	DBs
22	22	((substrate or wafer or device or plate) same ((spray$3 near9 coat$4) or (nozzle near12 spray$3) or dispens$5 or discharg$4) same (photoresist or resist)) and (((nozzle or spray) near26 (moving or rotat$4 or spin$4) near28 (vary$4 or variable or different) near29 (speed or velocity or velocit$4 or rate)) same (photoresist or resist) same (coat$3 or film or form$3 or deposit$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
23	18	((substrate or wafer or device or plate) same ((spray$3 near9 coat$4) or (nozzle near12 spray$3) or dispens$5 or discharg$4) same (photoresist or resist) same (across or diameter or center)) and (((nozzle or spray) near26 (moving or rotat$4 or spin$4) near28 (vary$4 or variable or different) near29 (speed or velocity or velocit$4 or rate)) same (photoresist or resist) same (coat$3 or film or form$3 or deposit$4 or layer))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
24	2	((substrate or wafer or device or plate) same ((spray$3 near9 coat$4) or (nozzle near12 spray$3) or dispens$5 or discharg$4) same (photoresist or resist)) and (((nozzle or spray) near26 (moving or rotat$4 or spin$4) near28 (vary$4 or variable or different) near29 (speed or velocity or velocit$4 or rate)) same (photoresist or resist) same (coat$3 or film or form$3 or deposit$4)) and ((substrate or wafer or template) near22 (circular or shape or geometr$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
25	25	((substrate or wafer or device or plate) same ((spray$3 near9 coat$4) or (nozzle near12 spray$3) or dispens$5) same (photoresist or resist or polymide or cur$4) same solution same (coat$3 or film or form$3 or deposit$4) same viscos$5) and ((substrate or wafer or platen or device) same surface same (prim$2 or (treat$5 near6 solution) or treat$4 or pre$3treat$4) same (nozzle or spray or dispens$4) same (rotat$4 or mov$5 or spin$4)) and ((substrate or wafer) same (rotat$4 or sin$4 or mov$5))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
26	0	((substrate or wafer or device or plate) same ((spray$3 near9 coat$4) or (nozzle near12 spray$3)) same (photoresist or resist or polymide) same solution same solid same (coat$3 or film or form$3 or deposit$4) same viscos$5 same centipoises)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
27	2	((substrate or wafer or device or plate) same ((spray$3 near9 coat$4) or (nozzle near12 spray$3)) same (photoresist or resist or polymide) same solution same (coat$3 or film or form$3 or deposit$4) same viscos$5 same centipoises)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
28	2	((substrate or wafer or device or plate) same ((spray$3 near9 coat$4) or (nozzle near12 spray$3)) same (photoresist or resist or polymide) same solution same (coat$3 or film or form$3 or deposit$4) same (viscos$5 near16 (centipoises or poises)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
29	3	((substrate or wafer or device or plate) same ((spray$3 near9 coat$4) or (nozzle near12 spray$3)) same (photoresist or resist or polymide) same (viscos$5 near16 (centipoises or poises)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
30	5	(((spray$3 near9 coat$4) or (nozzle near12 spray$3)) same (photoresist or resist or polymide) same (viscos$5 near16 (centipoises or poises)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
31	82	((coat$4 or film or form$4 or layer or spray$4) same (photoresist or resist or polymide) same (viscos$5 near16 (centipoises or poises)) same thickness)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB